

IN THE CLAIMS

Please amend the claims as follows:

Claims 1-6 (Canceled).

Claim 7 (Currently Amended): A high pressure processing apparatus for supplying a high pressure fluid to a processing object ~~to apply a high pressure processing to the processing object~~, the high pressure processing apparatus comprising:

a mounting table for supporting the processing object thereon;

a high pressure chamber adapted to contain the processing object therein, the high pressure chamber having a top ~~an introduction~~ wall positioned above an entire surface of the processing object on the mounting table and including ~~provided with~~ a fluid introduction passage connected to a source of fluid at a high pressure of at least 1MPa for introducing the high pressure fluid into the high pressure chamber, the high pressure chamber further having a side wall continuous with ~~integrally linked to~~ an outer peripheral part of the top ~~introduction~~ wall and extending down therefrom to surround ~~surrounding~~ the mounting table;

a rotating mechanism adapted to rotate the processing object together with the mounting table;

a fluid dispersion mechanism for dispersing the flow of the high pressure fluid to be supplied toward the surface of the processing object from the fluid introduction passage; and

a fluid discharger for allowing the high pressure fluid supplied from the fluid dispersion mechanism to the surface of the processing object, to be distributed radially outward along the surface of the processing object by the rotation of the processing object, and discharged outside the high pressure chamber, the fluid discharger including a fluid discharge passage provided in the sidewall of the high pressure chamber at an outward position relative to the processing object;

wherein the fluid dispersion mechanism includes a closure plate formed with a plurality of through holes and placed between the ~~top introduction~~ wall and the mounting table in opposed relation to the entire surface of the processing object on the mounting table and the ~~top introduction~~ wall, the closure plate being fitted to an internal surface of the side wall of the high pressure chamber so as to make a gap with the ~~top introduction~~ wall and allow the high pressure fluid introduced through the introduction passage to be supplied perpendicular to the surface of the processing object through the gap and each of the through holes.

Claim 8 (Currently Amended): The high pressure processing apparatus as claimed ~~defined~~ in claim 7, wherein the fluid supplier is adapted to supply a supercritical or subcritical fluid as the high pressure fluid to the processing object.

Claim 9 (Currently Amended): The high pressure processing apparatus as claimed ~~defined~~ in claim 7, wherein the fluid discharge passage is approximately parallel to the surface of the processing object, to discharge the high pressure fluid outside the high pressure chamber.

Claims 10-12 (Canceled).

Claim 13 (Previously Presented): The high pressure processing apparatus as claimed ~~defined~~ in claim 7, wherein the plurality of through holes are formed concentrically with respect to the center of the surface of the processing object, wherein the respective diameters of the through holes are arranged such that the high pressure fluid passes through the through holes at approximately the same flow rate, and the distance between the circumferentially

adjacent through holes is arranged such that it is reduced in the region of the closure plate opposed to the radially inward region of the surface of the processing object, more than in the region of the closure plate opposed to the peripheral region of the surface of the processing object.

Claims 14-15 (Canceled).

Claim 16 (Withdrawn): The high pressure processing apparatus as defined in claim 9, wherein the fluid discharge passage provided in the wall of the high pressure chamber at an outward position relative to the processing object and approximately parallel to the surface of the processing object is disposed in opposed relation to the peripheral edge of the processing object.

Claim 17 (Withdrawn): The high pressure processing apparatus as defined in claim 9, wherein the fluid introduction passage is provided in the wall of the high pressure chamber at a position opposed to the center of the surface of the processing object, wherein the wall of the high pressure chamber opposed to the surface of the processing object has a trumpet-shaped surface getting closer to the surface of the processing object in a direction oriented outward from the center of the surface of the processing object.

Claim 18 (Withdrawn): The high pressure processing apparatus as defined in claim 17, wherein the trumpet-shaped wall surface includes a hyperbolic surface.

Claim 19 (Withdrawn): The high pressure processing apparatus as defined in claim 17, wherein the trumpet-shaped wall surface is formed such that the distance from the center

of the surface of the processing object along the surface of the processing object is approximately in inverse proportion to the distance between the surface of the processing object and the trumpet-shaped wall surface.

Claim 20 (Canceled).

Claim 21 (Currently Amended): The high pressure processing apparatus as claimed ~~defined~~ in claim 7, wherein the fluid supplier is adapted to supply a supercritical fluid as the high pressure fluid to the processing object.

Claim 22 (New): The high pressure processing apparatus as claimed in claim 7, wherein the high pressure chamber is substantially cylindrical.